



## STATUS OF CLAIMS

1. (original) A curable adhesive composition comprising in combination:  
a curable silicone composition and contained in the curable silicone composition,  
  - (I) inorganic insulator particles having average particle size of 1  $\mu\text{m}$  to 1000  $\mu\text{m}$  and a major axis to minor axis ratio of about 1.0 to 1.5, said inorganic insulator particles being present in the adhesive composition in an amount sufficient to provide a planar adhesive bond thickness between substrates being joined by said adhesive, and
  - (II) at least one low coefficient of thermal expansion filler having an average particle size of less than 10 $\mu\text{m}$  in an amount of at least greater than 50 weight percent based on the weight of the curable silicone composition, wherein the low coefficient of thermal expansion fillers having sizes of greater than 10 to about 100 $\mu\text{m}$  are present in less than 0.1 weight percent based on the total weight of the low coefficient of thermal expansion fillers present in the adhesive composition.
2. (Original) A curable adhesive composition as claimed in claim 1 wherein the inorganic insulator particles are fused silica particles.
3. (Original) A curable adhesive composition as claimed in claim 1 wherein the inorganic insulator particles are alumina particles.
4. (Deleted) A semiconductor device in which at least two individual substrates are joined and bonded by an adhesive composition as claimed in claim 1.

5. (Amended) A process for joining at least two individual substrates, said process comprising:

- (I) applying an adhesive composition as claimed in claim 1 to at least one surface of at least one of the individual substrates;
- (II) mounting another individual substrate to the adhesive treated side of the substrate of (I) to form a laminate thereof;
- (III) applying pressure to the laminate to disperse the adhesive therebetween until each of the substrates contact the largest inorganic insulator particles of the adhesive composition, and thereafter,
- (IV) curing the adhesive composition.

6. (Original) The process as claimed in claim 5 wherein additionally, heat is applied in step (III).

7. (Once Amended) The semiconductor device as claimed in claim 15 wherein the two individual substrates are a semiconductor die and an attachment substrate for the semiconductor die.

8. (Original) The process as claimed in claim 5 wherein the two individual substrates are a semiconductor die and an attachment substrate for the semiconductor die.

9. (Deleted) The adhesive composition as claimed in claim 1 wherein the adhesive base material is selected from the group consisting essentially of:

- (a) a curable silicone composition;
- (b) a curable epoxy composition;
- (c) a curable polyimide composition, and,
- (d) a curable acrylic composition.

10. (Original) An adhesive composition as claimed in claim 1, having a cure mechanism selected from:

- (ii) condensation reactions;
- (iii) addition reactions;
- (iv) ultraviolet initiated radiation reactions, and,
- (v) free radical initiated reactions.

11. (Once amended) An adhesive composition as claimed in claim 9 wherein the adhesive base material is a silicone composition.

12. (Original) An adhesive composition as claimed in claim 1 wherein the silicone composition is an addition reaction curable silicone composition.

13. (Once amended) An adhesive composition as claimed in claim 9 wherein the adhesive base material is an epoxy composition.

14. (Deleted) An adhesive composition wherein insulating particles are present in an amount sufficient to obtain an adhesive with linear thermal expansion coefficient before and after any glass transition temperature of less than  $240 \mu\text{m}/\text{m}/^\circ\text{C}$ , between  $-55^\circ\text{C}$  and  $+200^\circ\text{C}$  when measured at a heating rate of  $5^\circ\text{C}/\text{minute}$ .

15. (New) A semiconductor device in which at least two individual substrates are joined and bonded by a curable adhesive composition, said curable adhesive composition comprising in combination a curable polymeric base material and contained in said polymeric base material,

(I) inorganic insulator particles having an average particle size of  $1 \mu\text{m}$  to  $1000 \mu\text{m}$  and a major axis to minor axis ratio of about 1.0 to 1.5, said inorganic insulator particles being present in the composition in an amount sufficient to provide a planar adhesive bond thickness between substrates being joined by said adhesive, and

(II) at least one low coefficient of thermal expansion filler having an average particle size of less than  $10 \mu\text{m}$  in an amount of at least greater than 50 weight percent based on the weight of the curable polymeric base material, wherein the low coefficient of thermal expansion fillers having sizes of greater than 10 to about  $100 \mu\text{m}$  are present in less than 0.1 weight percent based on the total weight of the low coefficient of thermal expansion fillers present in the adhesive composition.